

INFORMATION DISCLOSURE CITATION

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Applicant	Hiroshi NOMURA et al.		
Filing Date	Herewith	Prior Group:	2851

U.S. PATENT DOCUMENTS

Examiner Initial*	Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate
AM	4,908,656	03/1990	Suwa et al.	-		
AM	5,300,786	04/1994	Brunner et al.	-		
AM	5,789,118	08/1998	Liu et al.	-		
AM	5,948,571	09/1999	Mih et al.	-		
AM	6,011,611	01/2000	Nomura et al.	-		
AM	6,091,486	07/2000	Kirk	-		
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AM	6,130,747	10/2000	Nomura et al	-		
AM	6,171,739	01/2001	Spence et al.	-		
AM	6,310,679	10/2001	Shiraishi	-		

FOREIGN PATENT DOCUMENTS

	Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No
AM	11-237310	08/1999	Japan	-		No

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

AM	T.A. Brunner et al., " QUANTITATIVE STEPPER METROLOGY USING THE FOCUS MONITOR TEST MASK", Optical/Laser Microlithography VII, Timothy A. Brunner ed., Proc. SPIE, Vol. 2197, pp 541-549 (1994).
AM	J.P. Kirk et al., "APPLICATION OF BLAZED GRATINGS FOR DETERMINATION OF EQUIVALENT PRIMARY AZIMUTHAL ABERRATIONS", Optical Microlithography XII, Luc Van den Hove ed., Proc. SPIE. Vol. 3679, 70-76 (1999)
AM	Kirk, "ASTIGMATISM AND FIELD CURVATURE FROM PIN-BARS," March 6-8, 1991, SPIE, 1463:282-291

Examiner *Alan Mathews*Date Considered *12-9-2009*

*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.